

Grzegorz Greczynski

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/4740573/publications.pdf>

Version: 2024-02-01

157
papers

9,640
citations

70961

41
h-index

38300

95
g-index

161
all docs

161
docs citations

161
times ranked

7124
citing authors

#	ARTICLE	IF	CITATIONS
1	Morphology effects on electrocatalysis of anodic water splitting on nickel (II) oxide. <i>Microporous and Mesoporous Materials</i> , 2022, 333, 111734.	2.2	17
2	Dense, single-phase, hard, and stress-free Ti _{0.32} Al _{0.63} W _{0.05} N films grown by magnetron sputtering with dramatically reduced energy consumption. <i>Scientific Reports</i> , 2022, 12, 2166.	1.6	8
3	Undressing the myth of apparent constant binding energy of the C 1 s peak from adventitious carbon in x-ray photoelectron spectroscopy. , 2022, 1, 100007.		8
4	Improving oxidation and wear resistance of TiB ₂ films by nano-multilayering with Cr. <i>Surface and Coatings Technology</i> , 2022, 436, 128337.	2.2	4
5	Nano-columnar, self-organised NiCrC/a-C:H thin films deposited by magnetron sputtering. <i>Applied Surface Science</i> , 2022, 591, 153134.	3.1	2
6	Microstructure, mechanical, and corrosion properties of Zr _{1-x} Cr _x By diboride alloy thin films grown by hybrid high power impulse/DC magnetron co-sputtering. <i>Applied Surface Science</i> , 2022, 591, 153164.	3.1	3
7	Thermal, electrical, and mechanical properties of hard nitrogen-alloyed Cr thin films deposited by magnetron sputtering. <i>Surface and Coatings Technology</i> , 2022, 441, 128575.	2.2	6
8	High-entropy transition metal nitride thin films alloyed with Al: Microstructure, phase composition and mechanical properties. <i>Materials and Design</i> , 2022, 219, 110798.	3.3	8
9	Reprint of: Improving oxidation and wear resistance of TiB ₂ films by nano-multilayering with Cr. <i>Surface and Coatings Technology</i> , 2022, 442, 128602.	2.2	2
10	Domain epitaxial growth of Ta ₃ N ₅ film on c-plane sapphire substrate. <i>Surface and Coatings Technology</i> , 2022, 443, 128581.	2.2	4
11	A step-by-step guide to perform x-ray photoelectron spectroscopy. <i>Journal of Applied Physics</i> , 2022, 132, .	1.1	141
12	Oxidation kinetics of overstoichiometric TiB ₂ thin films grown by DC magnetron sputtering. <i>Corrosion Science</i> , 2022, 206, 110493.	3.0	17
13	Age hardening in superhard ZrB ₂ -rich Zr _{1-x} Ta _x By thin films. <i>Scripta Materialia</i> , 2021, 191, 120-125.	2.6	28
14	Towards reliable X-ray photoelectron spectroscopy: Sputter-damage effects in transition metal borides, carbides, nitrides, and oxides. <i>Applied Surface Science</i> , 2021, 542, 148599.	3.1	110
15	Multifunctional ZrB ₂ -rich Zr _{1-x} Cr _x By thin films with enhanced mechanical, oxidation, and corrosion properties. <i>Vacuum</i> , 2021, 185, 109990.	1.6	21
16	Orthorhombic Ta _{3-x} N _{5-y} O _y thin films grown by unbalanced magnetron sputtering: The role of oxygen on structure, composition, and optical properties. <i>Surface and Coatings Technology</i> , 2021, 406, 126665.	2.2	5
17	Phase Transformation and Superstructure Formation in (Ti _{0.5} , Mg _{0.5})N Thin Films through High-Temperature Annealing. <i>Coatings</i> , 2021, 11, 89.	1.2	2
18	X-ray photoelectron spectroscopy analysis of TiB _x (1.3 ≤ x ≤ 3.0) thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	0.9	7

#	ARTICLE	IF	CITATIONS
19	Dense Ti _{0.67} Hf _{0.33} B _{1.7} thin films grown by hybrid HfB ₂ -HiPIMS/TiB ₂ -DCMS co-sputtering without external heating. <i>Vacuum</i> , 2021, 186, 110057.	1.6	9
20	ZrCuAlNi thin film metallic glass grown by high power impulse and direct current magnetron sputtering. <i>Surface and Coatings Technology</i> , 2021, 412, 127029.	2.2	13
21	Phase formation and structural evolution of multicomponent (CrFeCo) _{1-y} Ny films. <i>Surface and Coatings Technology</i> , 2021, 412, 127059.	2.2	5
22	The same chemical state of carbon gives rise to two peaks in X-ray photoelectron spectroscopy. <i>Scientific Reports</i> , 2021, 11, 11195.	1.6	353
23	Preparation and tunable optical properties of amorphous AlSiO thin films. <i>Vacuum</i> , 2021, 187, 110074.	1.6	4
24	Toward energy-efficient physical vapor deposition: Routes for replacing substrate heating during magnetron sputter deposition by employing metal ion irradiation. <i>Surface and Coatings Technology</i> , 2021, 415, 127120.	2.2	23
25	Improved oxidation properties from a reduced B content in sputter-deposited TiB _x thin films. <i>Surface and Coatings Technology</i> , 2021, 420, 127353.	2.2	24
26	Influence of Si content on phase stability and mechanical properties of TiAlSiN films grown by AlSi-HiPIMS/Ti-DCMS co-sputtering. <i>Surface and Coatings Technology</i> , 2021, 427, 127661.	2.2	22
27	Study of Cucurbit[7]uril nanocoating on epitaxial graphene to design a versatile sensing platform. <i>Applied Surface Science</i> , 2021, 563, 150096.	3.1	2
28	Towards energy-efficient physical vapor deposition: Mapping out the effects of W ⁺ energy and concentration on the densification of TiAlWN thin films grown with no external heating. <i>Surface and Coatings Technology</i> , 2021, 424, 127639.	2.2	15
29	Systematic compositional analysis of sputter-deposited boron-containing thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	0.9	26
30	Thermally induced structural evolution and age-hardening of polycrystalline V _{1-x} MoxN (x=0.4) thin films. <i>Surface and Coatings Technology</i> , 2021, 405, 126723.	2.2	11
31	X-ray photoelectron spectroscopy: Towards reliable binding energy referencing. <i>Progress in Materials Science</i> , 2020, 107, 100591.	16.0	1,284
32	Surface functionalization of epitaxial graphene using ion implantation for sensing and optical applications. <i>Carbon</i> , 2020, 157, 169-184.	5.4	15
33	Cubic-structure Al-rich TiAlSiN thin films grown by hybrid high-power impulse magnetron co-sputtering with synchronized Al ⁺ irradiation. <i>Surface and Coatings Technology</i> , 2020, 385, 125364.	2.2	10
34	Effect of nitrogen content on microstructure and corrosion resistance of sputter-deposited multicomponent (TiNbZrTa) _{Nx} films. <i>Surface and Coatings Technology</i> , 2020, 404, 126485.	2.2	16
35	Improving the high-temperature oxidation resistance of TiB ₂ thin films by alloying with Al. <i>Acta Materialia</i> , 2020, 196, 677-689.	3.8	65
36	Self-organized columnar Zr _{0.7} Ta _{0.3} B _{1.5} core/shell-nanostructure thin films. <i>Surface and Coatings Technology</i> , 2020, 401, 126237.	2.2	15

#	ARTICLE	IF	CITATIONS
37	Cobalt thin films as water-recombination electrocatalysts. <i>Surface and Coatings Technology</i> , 2020, 404, 126643.	2.2	8
38	XPS guide: Charge neutralization and binding energy referencing for insulating samples. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	0.9	114
39	Electronic excitation of transition metal nitrides by light ions with keV energies. <i>Journal of Physics Condensed Matter</i> , 2020, 32, 405502.	0.7	1
40	Metal-ion subplantation: A game changer for controlling nanostructure and phase formation during film growth by physical vapor deposition. <i>Journal of Applied Physics</i> , 2020, 127, .	1.1	30
41	Oxidation behaviour of V2AlC MAX phase coatings. <i>Journal of the European Ceramic Society</i> , 2020, 40, 4436-4444.	2.8	33
42	High Si content TiSiN films with superior oxidation resistance. <i>Surface and Coatings Technology</i> , 2020, 398, 126087.	2.2	30
43	Microstructure and mechanical, electrical, and electrochemical properties of sputter-deposited multicomponent (TiNbZrTa)Nx coatings. <i>Surface and Coatings Technology</i> , 2020, 389, 125651.	2.2	37
44	Structural Modifications in Epitaxial Graphene on SiC Following 10 keV Nitrogen Ion Implantation. <i>Applied Sciences (Switzerland)</i> , 2020, 10, 4013.	1.3	7
45	Growth of dense, hard yet low-stress Ti0.40Al0.27W0.33N nanocomposite films with rotating substrate and no external substrate heating. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	0.9	13
46	Compromising Science by Ignorant Instrument Calibrationâ€”Need to Revisit Half a Century of Published XPS Data. <i>Angewandte Chemie</i> , 2020, 132, 5034-5038.	1.6	143
47	Compromising Science by Ignorant Instrument Calibrationâ€”Need to Revisit Half a Century of Published XPS Data. <i>Angewandte Chemie - International Edition</i> , 2020, 59, 5002-5006.	7.2	429
48	Structural and mechanical properties of amorphous AlMgB14 thin films deposited by DC magnetron sputtering on Si, Al2O3 and MgO substrates. <i>Applied Physics A: Materials Science and Processing</i> , 2020, 126, 1.	1.1	5
49	X-ray photoelectron spectroscopy studies of Ti1-Al N (0â€”â€”â€”â€”0.83) high-temperature oxidation: The crucial role of Al concentration. <i>Surface and Coatings Technology</i> , 2019, 374, 923-934.	2.2	64
50	Reactive magnetron sputtering of tungsten target in krypton/trimethylboron atmosphere. <i>Thin Solid Films</i> , 2019, 688, 137384.	0.8	6
51	A simple model for non-saturated reactive sputtering processes. <i>Thin Solid Films</i> , 2019, 688, 137413.	0.8	10
52	Paradigm shift in thin-film growth by magnetron sputtering: From gas-ion to metal-ion irradiation of the growing film. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	0.9	94
53	Quasi-amorphous, nanostructural CoCrMoC/a-C:H coatings deposited by reactive magnetron sputtering. <i>Surface and Coatings Technology</i> , 2019, 378, 124910.	2.2	7
54	Compositional dependence of epitaxial Tin+1SiCn MAX-phase thin films grown from a Ti3SiC2 compound target. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	0.9	8

#	ARTICLE	IF	CITATIONS
55	Strategy for simultaneously increasing both hardness and toughness in ZrB ₂ -rich Zr _{1-x} Ta _x By thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	0.9	42
56	Control over the Phase Formation in Metastable Transition Metal Nitride Thin Films by Tuning the Al+ Subplantation Depth. <i>Coatings</i> , 2019, 9, 17.	1.2	19
57	Corrosion Resistant TiTaN and TiTaAlN Thin Films Grown by Hybrid HiPIMS/DCMS Using Synchronized Pulsed Substrate Bias with No External Substrate Heating. <i>Coatings</i> , 2019, 9, 841.	1.2	5
58	Influence of Si doping and O ₂ flow on arc-deposited (Al,Cr) ₂ O ₃ coatings. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, 061516.	0.9	3
59	Electronic structure of $\hat{1}^2$ -Ta films from X-ray photoelectron spectroscopy and first-principles calculations. <i>Applied Surface Science</i> , 2019, 470, 607-612.	3.1	20
60	Effect of impurities on morphology, growth mode, and thermoelectric properties of (1 $\hat{1}$) and (0 $\hat{1}$) epitaxial-like ScN films. <i>Journal Physics D: Applied Physics</i> , 2019, 52, 035302.	1.3	31
61	Synthesis and characterization of single-phase epitaxial Cr ₂ N thin films by reactive magnetron sputtering. <i>Journal of Materials Science</i> , 2019, 54, 1434-1442.	1.7	16
62	Time evolution of ion fluxes incident at the substrate plane during reactive high-power impulse magnetron sputtering of groups IVb and VIb transition metals in Ar/N ₂ . <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	0.9	31
63	Substantial difference in target surface chemistry between reactive dc and high power impulse magnetron sputtering. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 05LT01.	1.3	10
64	Reliable determination of chemical state in x-ray photoelectron spectroscopy based on sample-work-function referencing to adventitious carbon: Resolving the myth of apparent constant binding energy of the C 1s peak. <i>Applied Surface Science</i> , 2018, 451, 99-103.	3.1	821
65	Controlling the B/Ti ratio of TiB _x thin films grown by high-power impulse magnetron sputtering. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	0.9	46
66	Enhanced Ti _{0.84} Ta _{0.16} N diffusion barriers, grown by a hybrid sputtering technique with no substrate heating, between Si(001) wafers and Cu overlayers. <i>Scientific Reports</i> , 2018, 8, 5360.	1.6	25
67	Chemical bonding in epitaxial ZrB ₂ studied by X-ray spectroscopy. <i>Thin Solid Films</i> , 2018, 649, 89-96.	0.8	20
68	Functionalization of bacterial cellulose wound dressings with the antimicrobial peptide $\langle i \rangle \hat{\mu} \langle /i \rangle$ -poly-L-Lysine. <i>Biomedical Materials (Bristol)</i> , 2018, 13, 025014.	1.7	86
69	Reference binding energies of transition metal carbides by core-level x-ray photoelectron spectroscopy free from Ar ⁺ etching artefacts. <i>Applied Surface Science</i> , 2018, 436, 102-110.	3.1	68
70	Highly Stable and Efficient Lignin \hat{e} PEDOT/PSS Composites for Removal of Toxic Metals. <i>Advanced Sustainable Systems</i> , 2018, 2, 1700114.	2.7	19
71	Modifications in structural, optical and electrical properties of epitaxial graphene on SiC due to 100 MeV silver ion irradiation. <i>Materials Science in Semiconductor Processing</i> , 2018, 74, 122-128.	1.9	10
72	Effect of ion-implantation-induced defects and Mg dopants on the thermoelectric properties of ScN. <i>Physical Review B</i> , 2018, 98, .	1.1	31

#	ARTICLE	IF	CITATIONS
73	Self-structuring in Zr _{1-x} Al _x N films as a function of composition and growth temperature. Scientific Reports, 2018, 8, 16327.	1.6	9
74	Electrical resistivity modulation of thermoelectric iron based nanocomposites. Vacuum, 2018, 157, 384-390.	1.6	3
75	Exploring NiO nanosize structures for ammonia sensing. Journal of Materials Science: Materials in Electronics, 2018, 29, 11870-11877.	1.1	19
76	V _{0.5} Mo _{0.5} N _x /MgO(001): Composition, nanostructure, and mechanical properties as a function of film growth temperature. Acta Materialia, 2017, 126, 194-201.	3.8	23
77	Unprecedented Al supersaturation in single-phase rock salt structure VAIN films by Al ⁺ subplantation. Journal of Applied Physics, 2017, 121, .	1.1	40
78	Controlling the boron-to-titanium ratio in magnetron-sputter-deposited TiB _x thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	40
79	Rolling performance of carbon nitride-coated bearing components in different lubrication regimes. Tribology International, 2017, 114, 141-151.	3.0	22
80	C _{1s} Peak of Adventitious Carbon Aligns to the Vacuum Level: Dire Consequences for Material's Bonding Assignment by Photoelectron Spectroscopy. ChemPhysChem, 2017, 18, 1507-1512.	1.0	695
81	Low-temperature growth of dense and hard Ti _{0.41} Al _{0.51} Ta _{0.08} N films via hybrid HIPIMS/DC magnetron co-sputtering with synchronized metal-ion irradiation. Journal of Applied Physics, 2017, 121, .	1.1	28
82	Comparative study of macro- and microtribological properties of carbon nitride thin films deposited by HiPIMS. Wear, 2017, 370-371, 1-8.	1.5	11
83	Control of the metal/gas ion ratio incident at the substrate plane during high-power impulse magnetron sputtering of transition metals in Ar. Thin Solid Films, 2017, 642, 36-40.	0.8	24
84	Gas rarefaction effects during high power pulsed magnetron sputtering of groups IVb and VIb transition metals in Ar. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	27
85	Native target chemistry during reactive dc magnetron sputtering studied by <i>ex-situ</i> x-ray photoelectron spectroscopy. Applied Physics Letters, 2017, 111, .	1.5	10
86	Ti ₂ Au ₂ C and Ti ₃ Au ₂ C ₂ formed by solid state reaction of gold with Ti ₂ AlC and Ti ₃ AlC ₂ . Chemical Communications, 2017, 53, 9554-9557.	2.2	53
87	ICMCTF 2017 " Preface. Surface and Coatings Technology, 2017, 332, 1.	2.2	0
88	Extended metastable Al solubility in cubic VAIN by metal-ion bombardment during pulsed magnetron sputtering: film stress <i>vs</i> subplantation. Journal of Applied Physics, 2017, 122, .	1.1	19
89	Core-level spectra and binding energies of transition metal nitrides by non-destructive x-ray photoelectron spectroscopy through capping layers. Applied Surface Science, 2017, 396, 347-358.	3.1	109
90	Selectable phase formation in VAIN thin films by controlling Al ⁺ subplantation depth. Scientific Reports, 2017, 7, 17544.	1.6	18

#	ARTICLE	IF	CITATIONS
91	Impact of B ₄ C co-sputtering on structure and optical performance of Cr/Sc multilayer X-ray mirrors. <i>Optics Express</i> , 2017, 25, 18274.	1.7	15
92	Improved adhesion of carbon nitride coatings on steel substrates using metal HiPIMS pretreatments. <i>Surface and Coatings Technology</i> , 2016, 302, 454-462.	2.2	37
93	Venting temperature determines surface chemistry of magnetron sputtered TiN films. <i>Applied Physics Letters</i> , 2016, 108, .	1.5	92
94	<i>In-situ</i> observation of self-cleansing phenomena during ultra-high vacuum anneal of transition metal nitride thin films: Prospects for non-destructive photoelectron spectroscopy. <i>Applied Physics Letters</i> , 2016, 109, .	1.5	26
95	TiN diffusion barrier failure by the formation of Cu ₃ Si investigated by electron microscopy and atom probe tomography. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2016, 34, .	0.6	13
96	Theoretical and experimental study of metastable solid solutions and phase stability within the immiscible Ag-Mo binary system. <i>Journal of Applied Physics</i> , 2016, 119, .	1.1	14
97	Nitrogen-doped bcc-Cr films: Combining ceramic hardness with metallic toughness and conductivity. <i>Scripta Materialia</i> , 2016, 122, 40-44.	2.6	41
98	Rolling contact fatigue of bearing components coated with carbon nitride thin films. <i>Tribology International</i> , 2016, 98, 100-107.	3.0	21
99	Self-consistent modelling of X-ray photoelectron spectra from air-exposed polycrystalline TiN thin films. <i>Applied Surface Science</i> , 2016, 387, 294-300.	3.1	131
100	Unintentional carbide formation evidenced during high-vacuum magnetron sputtering of transition metal nitride thin films. <i>Applied Surface Science</i> , 2016, 385, 356-359.	3.1	25
101	Novel transparent MgSiON thin films with high hardness and refractive index. <i>Vacuum</i> , 2016, 131, 1-4.	1.6	16
102	A comparative study of direct current magnetron sputtering and high power impulse magnetron sputtering processes for CN _x thin film growth with different inert gases. <i>Diamond and Related Materials</i> , 2016, 64, 13-26.	1.8	20
103	Peak amplitude of target current determines deposition rate loss during high power pulsed magnetron sputtering. <i>Vacuum</i> , 2016, 124, 1-4.	1.6	51
104	Synthesis and characterization of Zr ₂ Al ₃ C ₄ thin films. <i>Thin Solid Films</i> , 2015, 595, 142-147.	0.8	10
105	Stability of TiB ₄ C thin films under neutron radiation. <i>Radiation Physics and Chemistry</i> , 2015, 113, 14-19.	1.4	53
106	Novel hard, tough HfAlSiN multilayers, defined by alternating Si bond structure, deposited using modulated high-flux, low-energy ion irradiation of the growing film. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	0.9	7
107	Strategy for tuning the average charge state of metal ions incident at the growing film during HIPIMS deposition. <i>Vacuum</i> , 2015, 116, 36-41.	1.6	34
108	Al capping layers for nondestructive x-ray photoelectron spectroscopy analyses of transition-metal nitride thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	0.9	33

#	ARTICLE	IF	CITATIONS
109	Control of Ti _{1-x} Si _x N nanostructure via tunable metal-ion momentum transfer during HIPIMS/DCMS co-deposition. <i>Surface and Coatings Technology</i> , 2015, 280, 174-184.	2.2	53
110	Stoichiometric, epitaxial ZrB ₂ thin films with low oxygen-content deposited by magnetron sputtering from a compound target: Effects of deposition temperature and sputtering power. <i>Journal of Crystal Growth</i> , 2015, 430, 55-62.	0.7	33
111	Low-temperature growth of low friction wear-resistant amorphous carbon nitride thin films by mid-frequency, high power impulse, and direct current magnetron sputtering. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	0.9	17
112	Growth and properties of amorphous Ti _{0.6} Si _{0.4} N thin films deposited by hybrid HIPIMS/DC-magnetron co-sputtering from TiB ₂ and Si targets. <i>Surface and Coatings Technology</i> , 2014, 259, 442-447.	2.2	11
113	Novel strategy for low-temperature, high-rate growth of dense, hard, and stress-free refractory ceramic thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014, 32, .	0.9	45
114	A review of metal-ion-flux-controlled growth of metastable TiAlN by HIPIMS/DCMS co-sputtering. <i>Surface and Coatings Technology</i> , 2014, 257, 15-25.	2.2	126
115	Strain-free, single-phase metastable Ti _{0.38} Al _{0.62} N alloys with high hardness: metal-ion energy vs. momentum effects during film growth by hybrid high-power pulsed/dc magnetron cosputtering. <i>Thin Solid Films</i> , 2014, 556, 87-98.	0.8	69
116	X-ray Photoelectron Spectroscopy Analyses of the Electronic Structure of Polycrystalline Ti _{1-x} Al _x N Thin Films with 0 ≤ x ≤ 0.96. <i>Surface Science Spectra</i> , 2014, 21, 35-49.	0.3	20
117	Influence of inert gases on the reactive high power pulsed magnetron sputtering process of carbon-nitride thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2013, 31, .	0.9	18
118	Reactive high power impulse magnetron sputtering of CF _x thin films in mixed Ar/CF ₄ and Ar/C ₄ F ₈ discharges. <i>Thin Solid Films</i> , 2013, 542, 21-30.	0.8	17
119	Effect of substrate temperature on properties of diamond-like films deposited by combined DC impulse vacuum-arc method. <i>Surface and Coatings Technology</i> , 2013, 236, 444-449.	2.2	28
120	Influence of Ti _{0.6} Si _{0.4} N cathode grain size on the cathodic arc process and resulting Ti _{0.6} Si _{0.4} N coatings. <i>Surface and Coatings Technology</i> , 2013, 235, 637-647.	2.2	16
121	Sputter-cleaned Epitaxial V _x Mo _(1-x) Ny/MgO(001) Thin Films Analyzed by X-ray Photoelectron Spectroscopy: 3. Polycrystalline V _{0.49} Mo _{0.51} N _{1.02} . <i>Surface Science Spectra</i> , 2013, 20, 80-85.	0.3	8
122	Sputter-cleaned Epitaxial V _x Mo _(1-x) Ny/MgO(001) Thin Films Analyzed by X-ray Photoelectron Spectroscopy: 1. Single-crystal V _{0.48} Mo _{0.52} N _{0.64} . <i>Surface Science Spectra</i> , 2013, 20, 68-73.	0.3	12
123	Sputter-cleaned Epitaxial V _x Mo _(1-x) Ny/MgO(001) Thin Films Analyzed by X-ray Photoelectron Spectroscopy: 2. Single-crystal V _{0.47} Mo _{0.53} N _{0.92} . <i>Surface Science Spectra</i> , 2013, 20, 74-79.	0.3	11
124	Structural and mechanical properties of Cr _{0.4} Al _{0.6} O _{0.4} N thin films grown by cathodic arc deposition. <i>Acta Materialia</i> , 2012, 60, 6494-6507.	3.8	65
125	Metal versus rare-gas ion irradiation during Ti _{1-x} Al _x N film growth by hybrid high power pulsed magnetron/dc magnetron co-sputtering using synchronized pulsed substrate bias. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012, 30, .	0.9	98
126	Ion mass spectrometry investigations of the discharge during reactive high power pulsed and direct current magnetron sputtering of carbon in Ar and Ar/N ₂ . <i>Journal of Applied Physics</i> , 2012, 112, .	1.1	36

#	ARTICLE	IF	CITATIONS
127	Role of Ti^{n+} and Al^{n+} ion irradiation ($n=1, 2$) during $Ti_{1-x}Al_xN$ alloy film growth in a hybrid HIPIMS/magnetron mode. <i>Surface and Coatings Technology</i> , 2012, 206, 4202-4211.	2.2	119
128	Selection of metal ion irradiation for controlling $Ti_{1-x}Al_xN$ alloy growth via hybrid HIPIMS/magnetron co-sputtering. <i>Vacuum</i> , 2012, 86, 1036-1040.	1.6	66
129	Ti_3SiC_2 thin films grown by reactive arc evaporation from $Ti_{3/2}SiC_2$ cathodes. <i>Journal of Materials Research</i> , 2011, 26, 874-881.	1.2	19
130	CF_x thin solid films deposited by high power impulse magnetron sputtering: Synthesis and characterization. <i>Surface and Coatings Technology</i> , 2011, 206, 646-653.	2.2	43
131	Mitigating the geometrical limitations of conventional sputtering by controlling the ion-to-neutral ratio during high power pulsed magnetron sputtering. <i>Thin Solid Films</i> , 2011, 519, 6354-6361.	0.8	48
132	Microstructure evolution of Ti_3SiC_2 compound cathodes during reactive cathodic arc evaporation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2011, 29, 031601.	0.9	10
133	Industrial-scale deposition of highly adherent CN_x films on steel substrates. <i>Surface and Coatings Technology</i> , 2010, 204, 3349-3357.	2.2	33
134	Microstructure control of CrN_x films during high power impulse magnetron sputtering. <i>Surface and Coatings Technology</i> , 2010, 205, 118-130.	2.2	77
135	Time and energy resolved ion mass spectroscopy studies of the ion flux during high power pulsed magnetron sputtering of Cr in Ar and Ar/N_2 atmospheres. <i>Vacuum</i> , 2010, 84, 1159-1170.	1.6	116
136	CrN_x Films Prepared by DC Magnetron Sputtering and High-Power Pulsed Magnetron Sputtering: A Comparative Study. <i>IEEE Transactions on Plasma Science</i> , 2010, 38, 3046-3056.	0.6	72
137	Joint Theoretical and Experimental Characterization of the Structural and Electronic Properties of Poly(dioctylfluorene-alt-N-butylphenyl diphenylamine). <i>Journal of Physical Chemistry B</i> , 2004, 108, 5594-5599.	1.2	38
138	The effects of solvents on the morphology and sheet resistance in poly(3,4-ethylenedioxythiophene)-polystyrenesulfonic acid (PEDOT-PSS) films. <i>Synthetic Metals</i> , 2003, 139, 1-10.	2.1	702
139	Electronic structure of poly(9,9-dioctylfluorene) in the pristine and reduced state. <i>Journal of Chemical Physics</i> , 2002, 116, 1700-1706.	1.2	25
140	Hybrid interfaces in polymer-based electronics. <i>Synthetic Metals</i> , 2001, 121, 1625-1628.	2.1	10
141	Energy level alignment at polymer/electrode interfaces in light-emitting devices studied by photoelectron spectroscopy. , 2001, , .		1
142	Photoelectron spectroscopy of thin films of PEDOT-PSS conjugated polymer blend: a mini-review and some new results. <i>Journal of Electron Spectroscopy and Related Phenomena</i> , 2001, 121, 1-17.	0.8	389
143	An experimental study of poly(9,9-dioctyl-fluorene) and its interfaces with Al, LiF and CsF. <i>Applied Surface Science</i> , 2001, 175-176, 319-325.	3.1	14
144	The electronic structure of polymer-metal interfaces studied by ultraviolet photoelectron spectroscopy. <i>Materials Science and Engineering Reports</i> , 2001, 34, 121-146.	14.8	84

#	ARTICLE	IF	CITATIONS
145	Photoelectron spectroscopy study of the energy level alignment at polymer/electrode interfaces in light emitting devices. <i>Current Applied Physics</i> , 2001, 1, 98-106.	1.1	10
146	Hybrid interfaces of poly(9,9-dioctylfluorene) employing thin insulating layers of CsF: A photoelectron spectroscopy study. <i>Journal of Chemical Physics</i> , 2001, 114, 8628-8636.	1.2	32
147	Electronic structure of pristine and sodium doped poly(p-pyridine). <i>Journal of Chemical Physics</i> , 2001, 114, 4243-4252.	1.2	12
148	Photoelectron spectroscopy of hybrid interfaces for light emitting diodes: Influence of the substrate work function. <i>Applied Physics Letters</i> , 2001, 79, 3185-3187.	1.5	7
149	Photoelectron Spectroscopy of Interfaces for Polymer-Based Electronic Devices. , 2001, , .		1
150	Thin Interfacial Layers in Polymer-Based Electronics. <i>Materials Research Society Symposia Proceedings</i> , 2000, 660, .	0.1	0
151	Electronic structure of hybrid interfaces of poly(9,9-dioctylfluorene). <i>Chemical Physics Letters</i> , 2000, 321, 379-384.	1.2	40
152	Polymer interfaces studied by photoelectron spectroscopy: Li on polydioctylfluorene and Alq3. <i>Thin Solid Films</i> , 2000, 363, 322-326.	0.8	26
153	An experimental study of poly(9,9-dioctyl-fluorene) and its interface with Li and LiF.. <i>Applied Surface Science</i> , 2000, 166, 380-386.	3.1	16
154	Thin Interfacial Layers in Polymer-Based Electronics. <i>Materials Research Society Symposia Proceedings</i> , 2000, 660, 1.	0.1	0
155	Energy level alignment in organic-based three-layer structures studied by photoelectron spectroscopy. <i>Journal of Applied Physics</i> , 2000, 88, 7187-7191.	1.1	28
156	An experimental study of poly(9,9-dioctyl-fluorene) and its interfaces with Li, Al, and LiF. <i>Journal of Chemical Physics</i> , 2000, 113, 2407-2412.	1.2	89
157	Characterization of the PEDOT-PSS system by means of X-ray and ultraviolet photoelectron spectroscopy. <i>Thin Solid Films</i> , 1999, 354, 129-135.	0.8	390